

# United States Patent and Trademark Office

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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
09/993,575	11/06/2001	Sanjay Dabrat	05053.P001	8663	
8791 2	7590 11/04/2003	EXAMINER		INER	
BLAKELY SOKOLOFF TAYLOR & ZAFMAN 12400 WILSHIRE BOULEVARD, SEVENTH FLOOR			DEO, DUY	DEO, DUY VU NGUYEN	
LOS ANGELES, CA 90025			ART UNIT	PAPER NUMBER	
			1765		

DATE MAILED: 11/04/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
,	Application No.	, ,			
Office Action Summary	09/993,575	DABRAL ET AL.			
Office Action Summary	Examiner	Art Unit			
The MAN INC DATE of this communication con	DuyVu n Deo	1765			
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply					
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, - Any reply received by the Office later than three months after the mailing sarned patent term adjustment. See 37 CFR 1.704(b).  Status	36(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) day ill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
1) Responsive to communication(s) filed on 26 S	September 2003 .				
	is action is non-final.				
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213. <b>Disposition of Claims</b>					
4) Claim(s) 1-17 is/are pending in the application.					
4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.					
6)⊠ Claim(s) <u>1-17</u> is/are rejected.					
7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/or election requirement.					
Application Papers					
9) The specification is objected to by the Examiner.					
10)⊠ The drawing(s) filed on <u>06 November 2001</u> is/are: a)⊠ accepted or b)⊡ objected to by the Examiner.  Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner.					
If approved, corrected drawings are required in reply to this Office action.					
12) ☐ The oath or declaration is objected to by the Examiner.					
Priority under 35 U.S.C. §§ 119 and 120					
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).					
a) ☐ All b) ☐ Some * c) ☐ None of:		, , , , , , ,			
1. Certified copies of the priority documents	s have been received.				
2. Certified copies of the priority documents have been received in Application No					
Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).  * See the attached detailed Office action for a list of the certified copies not received.					
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).					
a) The translation of the foreign language provisional application has been received.					
15) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.					
Attachment(s)					
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449) Paper No(s)					

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### DETAILED ACTION

## Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- (e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) and the Intellectual Property and High Technology Technical Amendments Act of 2002 do not apply when the reference is a U.S. patent resulting directly or indirectly from an international application filed before November 29, 2000. Therefore, the prior art date of the reference is determined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

2. Claims 1, 2, 6, 10, 11 are rejected under 35 U.S.C. 102(e) as being anticipated by Wang et al. (US 2002/0077035 A1).

Wang describes a polishing pad comprising: a base layer (claimed base support layer), and an ion exchange material on the base (claimed ion exchange layer) (paragraph [0021]).

Referring to claims 2, 12, 13, the ion exchange materials can be polymer resins (paragraph [0034]) and in the form of beads [paragraph [0019]). Also, the ion exchange particles

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are embedded or impregnated in a porous polymeric layer (paragraph [0044]). This would read on claimed ion exchange resin beads and a resin layer having ion exchange material embedded therein.

Referring to claims 10 and 11, the ion exchange layer binds cations including copper ions (paragraphs [0032], [0036]).

### Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 7-9, 15-17 are rejected under 35 U.S.C. 103(a) as being unpatentable over Wang as applied to claims 1, 6, 12 above, and further in view of Agarwal et al. (US 6,206,759).

Unlike claimed invention, Wang doesn't describe the pad having the base and ion exchange layer patterned. Agarwal describes a polishing pad that is patterned to the base (col. 10, line 1-27). It would have been obvious for one skill in the art at the time of the invention to pattern the polishing pad, including patterning the base and the ion exchange layer because Wang describes that the conventional polishing pads comprise grooves to convey the slurry to the wafer while undergoing CMP (paragraph [0008]) and Agarwal teaches that patterning the pad to form grooves for transporting planarizing solution and provide sufficient flexibility to the pad (col. 10, line 4-6, 12, 13).

5. Claims 3-5, 14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Wang.

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Referring to claims 3 and 14, even though Wang doesn't describe the ion exchange layer comprises ground ion exchange beads or ion exchange powder; however, he suggests that the ion exchange resin can be in a variety of different physical forms depending primarily on the form of the initial matrix resin (paragraph [0037], [0039]). Therefore, at the time of the invention, using other forms of the ion exchange resin such as claimed ground or powder would have been obvious with a reasonable expectation of success.

Referring to claims 4 and 5, using any method such as pressing the ion exchange beads into the ion exchange layer would be obvious because Wang describes that the ion exchange material is embedded or impregnated in the ion exchange layer (paragraph [0044]). Furthermore, these claims do not carry patentable weight since they do not describe structural parts of the apparatus as claimed but method for forming the apparatus.

### Claim Rejections - 35 USC § 112

- 6. The following is a quotation of the second paragraph of 35 U.S.C. 112:
  The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.
- 7. Claim 17 recites the limitations "the polishing layer" and "the support layer." There is insufficient antecedent basis for this limitation in the claim.

#### Election/Restrictions

- 8. Applicant's election without traverse of claims 1-17 in the paper filed 9/26/03 is acknowledged.
- 9. Any inquiry concerning this communication or earlier communications from the examiner should be directed to DuyVu n Deo whose telephone number is 703-305-0515.

DVD 10/28/03 ().